

AMENDMENTS TO THE CLAIMS

Claims 1-13 (Cancelled)

14. (Currently Amended) A method of forming a semiconductor device, the method comprising:

forming a layer of conductive material on a conductive region and a layer of insulation material;

etching the layer of conductive material to form a trace, the trace having a first length, a first width, a first height, a top surface and a bottom surface;

etching the trace to form a slot opening in the top surface of the trace, the slot opening having a conductive bottom surface ~~spaced apart from that completely lies above~~ the bottom surface of the trace, a second length, a second width, and a second height, the first and second lengths being substantially equal; and

forming a layer of isolation material over the trace to fill up the slot opening, the layer of isolation material contacting the conductive bottom surface of the slot opening.

15. (Original) The method of claim 14 wherein the trace is formed to have a number of loops.

16. (Original) The method of claim 15 wherein the loops lie substantially in a same plane.

17. (Original) The method of claim 14 wherein the trace is connected to a contact.

18. (Original) The method of claim 14 wherein the trace is connected to a via.

19. (Previously Presented) The method of claim 14 wherein the layer of isolation material contacts the layer of insulation material.

20. (Previously Presented) The method of claim 14 wherein the conductive material is metal.

Claims 21-22 (Cancelled)

23. (Currently Amended) A method of forming a semiconductor device, the method comprising:

forming a layer of conductive material on a conductive region and a layer of insulation material;

etching the layer of conductive material to form a trace, the trace having a length, a width, a height, a top surface, and a bottom surface;

etching the trace to form a slot opening in the top surface of the trace, the slot opening having a conductive bottom surface ~~spaced apart from~~ that completely lies above the bottom surface of the trace, and side walls that extend along the length of the trace; and

forming a layer of isolation material over the trace to fill up the slot ~~openings~~ opening, the layer of isolation material contacting the conductive bottom surface of the slot opening.

24. (Previously Presented) The method of claim 23 wherein the trace is formed to have a number of loops.

25. (Previously Presented) The method of claim 24 wherein the loops lie substantially in a same plane.

26. (Previously Presented) The method of claim 23 wherein the layer of isolation material contacts the layer of insulation material.

27. (Previously Presented) The method of claim 23 wherein the conductive material is metal.

28. (Previously Presented) The method of claim 23 wherein the slots are substantially equally spaced apart.

29. (Currently Amended) A method of forming a semiconductor device, the method comprising:

forming a layer of conductive material on a conductive region and a layer of insulation material;

etching the layer of conductive material to form a trace, the trace having a bottom surface and a substantially planar top surface;

etching the trace to form a plurality of slot openings in the top surface of the trace, each slot opening having a conductive bottom surface ~~spaced apart from that completely lies above~~ the bottom surface of the trace, a portion of each slot opening lying directly vertically over the conductive region; and

forming a layer of isolation material over the trace to fill up the slot openings, the layer of isolation material contacting the conductive bottom surface of each slot opening.

30. (Previously Presented) The method of claim 29 wherein the trace is formed to have a number of loops.

31. (Previously Presented) The method of claim 30 wherein the loops lie substantially in a same plane.
32. (Currently Amended) The method of claim 29 wherein the ~~metal~~ conductive region is a via.
33. (Previously Presented) The method of claim 29 wherein the layer of isolation material contacts the layer of insulation material.
34. (Previously Presented) The method of claim 29 wherein the conductive material is metal.
35. (Previously Presented) The method of claim 29 wherein the slots are substantially equally spaced apart.